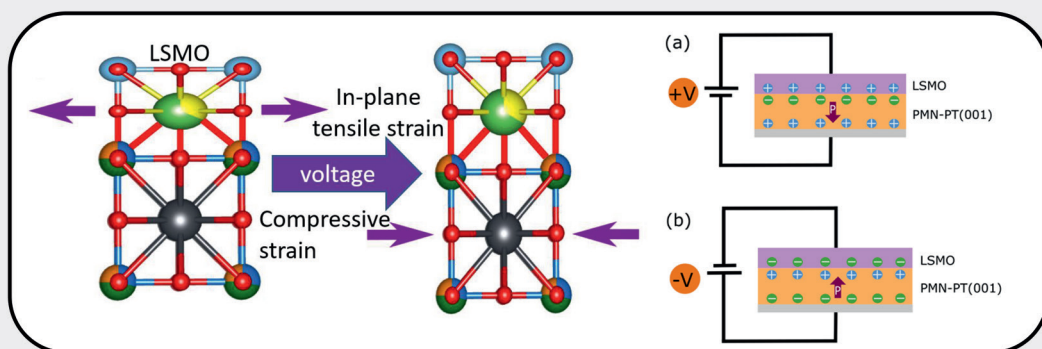
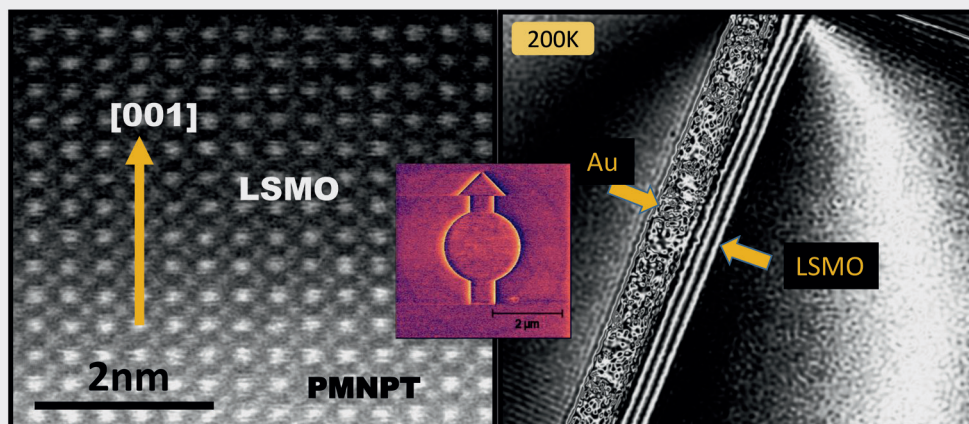




Resolving interface effects in voltage controlled magnetic heterostructures using advanced neutron scattering and electron microscopy methods

Tanvi Bhatnagar-Schöffmann

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